Contents

List of Contributors ix
Treatise Preface xi
Preface xiii

1 Heavy Ion Charge States
Hans D. Betz

I. Introduction 2
II. Basic Processes and Mathematical Description of Charge Exchange 5
III. Experimental Aspects 11
IV. Electron Capture 16
V. Electron Loss 22
VI. Equilibrium Charge-State Distributions 26
VII. Gas and Solid Effects 35
References 37

2 Ionization Phenomena and Sources of Ions
G. D. Alton

I. Introduction 44
II. Ion Source Selection Considerations 46
III. Vapor Transport Methods 50
IV. Positive Ionization Phenomena and Sources 54
V. Negative Ionization Phenomena and Sources 128
VI. Ion Extraction and Optics of the Extraction Region 157
References 171

3 Radiation Physics as a Basis of Radiation Chemistry and Biology
Mitio Inokuti

I. What are the Problems of Radiation Physics? 179
II. Problems of Class I: How Do Radiations Degrade in Matter? 184
III. Problems of Class II: How Does Matter Change after Receiving Energy from Radiation? 194
IV. Some Notions of Radiation Chemistry and Biology 220
V. Concluding Remarks 228
References 229

4 Low Energy Ion Scattering and Atomic Diffraction
W. Heiland and E. Taglauer

I. Ion Scattering Spectrometry (ISS) 238
II. Scattering of Atomic Beams at Thermal Energies 250
References 258

5 High Energy Ion Scattering
L. C. Feldman

I. Introduction 261
II. Physics of Ion Scattering in Amorphous Solids 262
III. Atomic Composition of Surface Layers 267
IV. MeV Ion Scattering in Single Crystals 274
V. Structure Analysis in Crystalline Solids 282
VI. Summary 297
References 297

6 Inelastic Surface Collisions
Edward W. Thomas

I. Introduction 299
II. Ion-Induced Auger Spectra 300
III. Ion Neutralization at Surfaces 305
IV. Excitation of Projectiles 314
V. Optical Emission for Target Species 318
VI. Conclusion 322
References 323

7 Secondary Ion Mass Spectrometry
Peter Williams

I. Introduction 327
II. The Sputtering Process 329
III. Sputtered Ion Emission: Phenomena and Models 336
IV. Instrumentation 348
V. Applications of Secondary Ion Mass Spectrometry 353
VI. Conclusion 374
References 375

8 The Time-of-Flight Atom Probe and Field Ion Microscopy
T. T. Tsong

I. Introduction 380
II. Basic Principles 382
III. Field Ion Microscope and Atom-Probe FIM 384
IV. Atomic Processes on Solid Surfaces 392
V. Atom-Probe Analyses 399
VI. Summary 405
References 405

9 Ion-Induced X-Ray Emission
S. Raman

I. Introduction 407
II. Coulomb Ionization 408
III. Proton-Induced X-Ray Emission (PIXE) 412
IV. Heavy-Ion-Induced X-Ray Emission 420
References 426

10 X-Ray Fluorescence Analysis
C. J. Sparks, Jr.

I. Introduction 429
II. Development of the Physics 433
III. Development of the Analytical Application 436
IV. Comparison to Other Analytical Techniques 441
V. X-Ray Fluorescence Analysis in Industry 443
VI. Conclusions 446
References 447

11 Photoelectron and Auger Spectroscopy
Stig B. Hagström, Manfred O. Krause, and Steven T. Manson

I. Introduction 450
II. Description of the Processes 451
III. Experimental Considerations 464
IV. Applications 486
References 538

12 Ion Implantation in Semiconductors
James W. Mayer and Jozsef Gyulai

I. Introduction 545
II. Depth Distributions in Implanted and Annealed Samples 547
III. Implantation Damage 551
IV. Electrical Activity 560
V. Recoil Implantation 563
VI. Annealing of Disorder by Irradiation 566
VII. Summary 571
References 571

13 Microfabrication
J. W. Coburn

I. Introduction 577
II. Microfabrication Processes 578
III. Pattern Replication (Lithography) 582
IV. Pattern Transfer 597
V. Discussion 605
References 608

Index 613